



Atty. Dkt. No. 017447-0194

*IN THE UNITED STATES PATENT AND TRADEMARK OFFICE*

Applicant: Koichi WATANABE et al.  
Title: SPUTTERING TARGET AND PROCESS FOR PRODUCING Si OXIDE FILM THEREWITH  
Appl. No.: 10/573,406  
International Filing Date: 9/22/2004  
371(c) Date: 3/27/2006  
Examiner: Jason Berman  
Art Unit: 1795  
Confirmation Number: 2973

AMENDMENT AND REPLY UNDER 37 CFR 1.111

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

This communication is responsive to the Non-Final Office Action dated November 13, 2009, concerning the above-referenced patent application.

Applicant has enclosed with this amendment a Petition for Extension of Time to make this response timely.

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this document.

**Remarks** begin on page 4 of this document.

Please amend the application as follows: